


Substitute Form PTO-1449 (Modified)	U.S. Department of Commerce Patent and Trademark Office	Attorney's Docket No. 14580-034001	Application No. 10/676,360
Information Disclosure Statement by Applicant (Use several sheets if necessary) (37 CFR §1.98(b))		Applicant Haoren Zhuang et al.	
		Filing Date September 30, 2003	Group Art Unit 2811

U.S. Patent Documents							
Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
TTN	AA	2003/0082916	05/2003	Chung, et al.			
	AB	2003/0119251	06/2003	Aggarwal, et al.			
	AC	5,972,722	10/1999	Visokay, et al.			
	AD	6,211,034	04/2001	Visokay, et al.			
	AE	6,465,321	10/2002	Shin, et al.			
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						

Foreign Patent Documents or Published Foreign Patent Applications								
Examiner Initial	Desig. ID	Document Number	Publication Date	Country or Patent Office	Class	Subclass	Translation	
							Yes	No
	AL							
	AM							
	AN							
	AO							
	AP							

Other Documents (include Author, Title, Date, and Place of Publication)		
Examiner Initial	Desig. ID	Document
TTN	AQ	"Sputter-Resistant Mask Structure and Process", IBM Technical Disclosure Bulletin, IBM Corp., New York, USA, 33(3B):379-381, August 1990.
	AR	
	AS	
	AT	

Examiner Signature 	Date Considered 03/02/2005
EXAMINER: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	